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 PALM INTRANET

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L Number	Hits	Search Text	DB	Time stamp
1	1906041	photosensitive resin composition and polyimide and (photosensitizer or initiator)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:18
2	382974	((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:19
3	376746	((((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:20
4	29796	(((((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:21
5	0	((((((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane) and ?diaminocyclohexane	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:21
6	0	((((((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane) and ?methylenebiscyclohexane	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:31
8	26	((((((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane) and 522/164.ccls.) and (polyamic acid or polyimide precursor or polyamide acid)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:22
9	22	((((((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane) and 522/164.ccls.) and (polyamic acid or polyimide precursor or polyamide acid)) and (film or layer)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:23
11	556604	((((((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane) and 522/164.ccls.) and (polyamic acid or polyimide precursor or polyamide acid)) and (film or layer)) and alicyclic) and sulfonic ester	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:23
10	11	((((((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane) and 522/164.ccls.) and (polyamic acid or polyimide precursor or polyamide acid)) and (film or layer)) and alicyclic	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:23
7	26	(((((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane) and 522/164.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:30
12	1730	(((((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane) and (polyamic acid or polyimide precursor) and photoinitiator	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:31

13	2	((((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane) and (polyamic acid or polyimide precursor) and photoinitiator) and imidiz?	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:34
14	3	((((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane) and (polyamic acid or polyimide precursor) and photoinitiator) and ?cyclohexane	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:36
15	40	((((photosensitive resin composition and polyimide and (photosensitizer or initiator)) and o quinone diazide) and (?trihydroxybenzophenone o naphthoquinone diazide sulfonic ester)) and cyclohexane) and (polyamic acid or polyimide precursor) and photoinitiator) and methylene near3 cyclohexane	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/08/10 16:42
16	174	(522/164).CCLS.	USPAT	2004/08/10 17:07